PCN Nun	ıber:	201	3071500	1			PCN Dat	e: 07/25/2013	
Title:					np – Carsem Su 2965xxx device		(CSZ) as a	additional Fab site	
Customer Contact: PC			Manager Phone: +1(214)480-6037			7 Dept:	Quality Services		
			10/25/	013 Estimated Sample Availability:		·	Date provided a sample request.		
Change 1									
Assembly Site			Assembly Process						
				rical Spec			Mechanical Specification		
					ing/Labeling		Test Proc		
	er Bump Site			r Bump N		14		mp Process	
🛛 🛛 Waf	er Fab Site		🖄 🛛 Wafe	r Fab Mat			Wafer Fal	o Process	
				PCN	Details				
Descripti	ion of Chang	e:							
Test site o		Wafer TPS22	Bump si 2965DSC	te and Ca		(CSZ) levice	as an addi s. Material	tional Assembly / differences are	
Test site of shown in	option for the the following	Wafer TPS22	Bump si 2965DSC	te and Ca R and TP	arsem Suzhou (S22965DSGT c RK	(CSZ) levice Car	as an addi s. Material	tional Assembly / differences are	
Test site of shown in Mold Cor	option for the the following	Wafer TPS22	Bump si 2965DSC	te and Ca R and TP TI CLA 420862	RK	(CSZ) device Car G72	as an addi s. Material sem Suzh 70HCD	tional Assembly / differences are	
Test site of shown in Mold Cor Mount Co	pption for the the following mpound ompound	Wafer TPS22	Bump si 2965DSC	te and Ca R and TP TI CLA 420862 420776	RK 88 88 88	(CSZ) levice Car 649	as an addi s. Material sem Suzh 70HCD 91681	tional Assembly / differences are	
Test site of shown in Mold Cor Mount Co Bond Win	mpound ompound re	Wafer TPS22 table:	Bump si 2965DSC	te and Ca R and TP TI CLA 420862 420776 1.98 Mi	RK RK IDia., Cu	(CSZ) device Car 649 2.0	as an addi s. Material sem Suzh 70HCD 91681 mil Diame	tional Assembly / differences are	
Test site of shown in Mold Cor Mount Co Bond Win Leadfran	pption for the the following mpound ompound	Wafer TPS22 table: 	Bump si 2965DSG	te and Ca R and TP TI CLA 420862 420776 1.98 Mi NiPdAu	RK RK IDia., Cu	(CSZ) device Car 649 2.0	as an addi s. Material sem Suzh 70HCD 91681	tional Assembly / differences are	
Test site of shown in Mold Cor Mount Co Bond Win Leadfran Wafer Dia	mpound ompound re ne (Finish, Bas	Wafer TPS22 table: se) e is sh	Bump si 2965DSG	te and Ca R and TP TI CLA 420862 420776 1.98 Mi NiPdAu	RK RK IDia., Cu	CSZ) device G72 649 2.0 NiP	as an addi s. Material sem Suzh 70HCD 91681 mil Diame dAu	tional Assembly / differences are	
Test site of shown in Mold Cor Mount Co Bond Win Leadfran Wafer Dia Currently	mpound ompound re ne (Finish, Base ometer change	Wafer TPS2: table: se) e is sh e, Pro	Bump si 2965DSG own belo pcess, Wa	te and Ca R and TP TI CLA 420862 420776 1.98 Mi NiPdAu	RK RK IDia., Cu	CSZ) device Car G72 649 2.0 NiP	as an addi s. Material sem Suzh 70HCD 91681 mil Diame dAu Process,	tional Assembly / differences are ou ter, Cu Wafer Dia.	
Test site of shown in Mold Cor Mount Co Bond Win Leadfran Wafer Dia Currently RFAB, LE	pption for the the following mpound ompound re ne (Finish, Bas meter change y Qualified Sit 3C7 Process, 3	Wafer TPS2: table: se) e is sh e, Pro 300mr	Bump si 2965DSG own belo ocess, Wa n	te and Ca R and TP TI CLA 420862 420776 1.98 Mi NiPdAu w: ifer Dia.	RK ARK ARK ARK ARK ARK ARK ARK A	CSZ) device G7 G7 G7 G7 G7 G7 G7 G7 G7 G7 Site, NiP	as an addi s. Material sem Suzh 70HCD 91681 mil Diame dAu Process, 20	tional Assembly / differences are ou ter, Cu Wafer Dia.	
Test site of shown in Mold Cor Mount Co Bond Win Leadfran Wafer Dia Currently RFAB, LE Test cove test MQ. Reason f	mpound ompound re ne (Finish, Bas y Qualified Sit BC7 Process, 3 rage, insertion	Wafer TPS2: table: se) e is sh e, Pro 300mr	Bump si 2965DSG own belo ocess, Wa n	te and Ca R and TP TI CLA 420862 420776 1.98 Mi NiPdAu w: ifer Dia.	RK ARK ARK ARK ARK ARK ARK ARK A	CSZ) device G7 G7 G7 G7 G7 G7 G7 G7 G7 G7 Site, NiP	as an addi s. Material sem Suzh 70HCD 91681 mil Diame dAu Process, 20	tional Assembly / differences are ou ter, Cu Wafer Dia. 00mm	
Test site of shown in Mold Cor Mount Co Bond Win Leadfran Wafer Dia Currently RFAB, LE Test cove test MQ. Reason f Continuity	pption for the the following mpound ompound re ne (Finish, Base meter change y Qualified Sit 3C7 Process, 3 rage, insertion for Change: y of Supply	Wafer TPS2: table: se) e is sh e, Pro 300mr ns, co	Bump si 2965DSG own belo ocess, Wa n nditions v	te and Ca R and TP TI CLA 420862 420776 1.98 Mi NiPdAu w: ifer Dia.	Arsem Suzhou (S22965DSGT c RK 25 88 Il Dia., Cu Additional MIHO8, Li in consistent wi	CSZ) device Car G7 G7 G7 C G7 C G7 C G7 C G7 C C C T C C C C C C C C C C C C C C C	as an addi s. Material sem Suzh 70HCD 91681 mil Diame dAu Process, 20 rrent testin	tional Assembly / differences are ter, Cu Wafer Dia. 00mm g and verified wit	
Test site of shown in Mold Cor Mount Co Bond Win Leadfran Wafer Dia Currently RFAB, LE Test cove test MQ. Reason f Continuity	pption for the the following mpound ompound re ne (Finish, Base meter change y Qualified Sit 3C7 Process, 3 rage, insertion for Change: y of Supply	Wafer TPS2: table: se) e is sh e, Pro 300mr ns, co	Bump si 2965DSG own belo ocess, Wa n nditions v	te and Ca R and TP TI CLA 420862 420776 1.98 Mi NiPdAu w: ifer Dia.	Arsem Suzhou (S22965DSGT c RK 25 88 Il Dia., Cu Additional MIHO8, Li in consistent wi	CSZ) device Car G7 G7 G7 C G7 C G7 C G7 C G7 C C C T C C C C C C C C C C C C C C C	as an addi s. Material sem Suzh 70HCD 91681 mil Diame dAu Process, 20 rrent testin	tional Assembly / differences are ou ter, Cu Wafer Dia. 00mm	

Changes to product identification resulting from this PCN:

Shipment Labels:

Current

Chip Site	Chip site code (20L)	Chip country code (21L)
RFAB	RFB	USA

New

Chip Site	Chip site code (20L)	Chip country code (21L)
MIHO8	MH8	JPN

Current

Assembly Site	Assembly site Origin (22L)	Assembly country Origin (23L)
TI CLARK - Philippines	QAB	PHL

New

Assembly Site	Assembly site Origin (22L)	Assembly country Origin (23L)
Carsem Suzhou	CSZ	CHN

Device Marking for TI Clark and Carsem Suzhou are the same.

Assembly site code for TI Clark = I

Assembly site code for Carsem Suzhou = F

Sample product shipping label (not actual product label)



Product Affected:		
TPS22965DSGR	TPS22965DSGT	

Qualification Data: (Approved: 7/11/2013)						
This qualification has been developed for the validation of this change. The qualification data will						
validate that the proposed change meets the applicable released technical specifications.						
Qualification Device: TPS22965DSGR						
Wafer Fab Site: MIHO 8					Carsem Suzhou	
Wafer Fab Process: LBC7			# Pins-Designator:	8-D3	SG	
Wafer diameter:	200mm	Package Family:		DSG		
Metallization:	TiN/AlCu.5/TiN	Lea	ad Frame (Finish, Base):	NiPdAu, Cu		
Passivation: PECVDOX/NITRIDE					.0 Mil Dia., Cu	
Qualification:	Plan 🛛 🛛 Test Resu	lts	-			
Reliability Test			Conditions		Sample Size /Fail	
Electrical Characterization – Limit Verification		n	Per datasheet spec		Pass	
ESD HBM			1000V		3/0	
ESD CDM			250V		3/0	
Physical Dimensions			Per mechanical drawing		5/0	
Bond Strength			76 ball bonds		76/0	
Die Shear			-		8/0	
Latch-up			(per JESD78)		6/0	
**Preconditioning: MSL 2@260C						

For questions regarding this notice, e-mails can be sent to the regional contacts shown below, or you can contact your local Field Sales Representative.

Location	E-Mail
USA	PCNAmericasContact@list.ti.com
Europe	PCNEuropeContact@list.ti.com
Asia Pacific	PCNAsiaContact@list.ti.com
Japan	PCNJapanContact@list.ti.com